

	Hits	Search Text	DBs
44	36	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) and (resin\$3 same (cyclic or water\$3soluble or alkali\$3soluble or aromatic or alicyclic or heterocyclic or polyphenol or naphthalene\$3polyhydroxy or benzophenone or flavonoid or polycycloalkane or (aromatic near3 carboxylic) or cycloalkane) same ((alkali\$3 or water) near2 solub\$5)) and (surfactant near23 (nonionic or anionic or amphoteric or cationic) near29 ((primary near5 alcohol near6 ethoxylate) or (phenol near6 ethoxylate)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
45	1	((resist or photoresist) near16 (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) same adamantanol) and (surfactant near23 (nonionic or anionic or amphoteric or cationic) near29 ((primary near5 alcohol near6 ethoxylate) or (phenol near6 ethoxylate)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
46	56	((resist or photoresist) near16 (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) same adamantanol)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
47	69	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material)) same (surfactant)) and (surfactant near23 (nonionic or anionic or amphoteric or cationic) near29 ((primary near5 alcohol near6 ethoxylate) or (phenol near6 ethoxylate)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
48	36	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) and (resin\$3 same (cyclic or water\$3soluble or alkali\$3soluble or aromatic or alicyclic or heterocyclic or polyphenol or naphthalene\$3polyhydroxy or benzophenone or flavonoid or polycycloalkane or (aromatic near3 carboxylic) or cycloalkane) same ((alkali\$3 or water) near2 solub\$5)) and (surfactant near23 (nonionic or anionic or amphoteric or cationic) near29 ((primary near5 alcohol near6 ethoxylate) or (phenol near6 ethoxylate)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
49	40	S50 NOT S51	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
50	151	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) and (surfactant near23 (nonionic or anionic or amphoteric or cationic) near29 ((primary near5 alcohol near6 ethoxylate) or (phenol near6 ethoxylate)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
51	69	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material)) same (surfactant)) and (surfactant near23 (nonionic or anionic or amphoteric or cationic) near29 ((primary near5 alcohol near6 ethoxylate) or (phenol near6 ethoxylate)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
52	82	S53 NOT S54	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
53	295	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) and (surfactant near29 ((primary near5 alcohol near6 ethoxylate) or (phenol near6 ethoxylate)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
54	144	S56 NOT S53	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
55	22	"430"/\$.ccls. and S57	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB